

Rapidly counting atomic planes of ultra-thin MoSe₂ nanosheets $(1 \le n \le 4)$ on SiO₂/Si substrate

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Abstract The optical, thermal and electrical properties of ultra-thin two-dimensional (2D) crystal materials are highly related to their thickness. Therefore, identifying the atomic planes of few-layer crystal materials rapidly is crucial to fundamental study. Here, a simple technique was demonstrated based on optical contrast for counting atomic planes (n) of few-layer $MoSe_2$ on SiO_2/Si substrates. It is found that the optical contrast of single-layer MoSe₂ depends on light wavelength and thickness of SiO₂ on Si substrate. The data calculated based on a Fresnel law-based model as well as atomic force microscopy (AFM) measurements fit well with the values measured by spectroscopic ellipsometer. Furthermore, the calculated and measured contrasts were integral and plotted, which can be used to determine the MoSe₂ atomic planes $(1 \le n \le 4)$ accurately and rapidly.

Keywords Thickness identification; Optical contrast; MoSe₂; Optical microscopy

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1 Introduction

Since the discovery of mechanical exfoliated graphene in Manchester in 2004 [1, 2], two-dimensional (2D) materials have attracted much interest [3]. However, graphene does not have a native bandgap, leading to the prosperity of other 2D semiconducting materials, such as the transition-metal dichalogenides [4-7]. Transition-metal dichalogenides have demonstrated many extraordinary optical, thermal, magnetic and electrical properties and are ready for various applications [8–10]. Recently, single-layer MoSe₂ has been exfoliated onto SiO₂/Si substrate. Determined by photoluminescence measurements, MoSe₂ displayed good thermal stability with a direct bandgap of 1.55 eV [11]. In addition, single-layer MoSe₂ was proved to have electrocatalytic activity [8]. Like graphene, these properties are highly related to thickness [8, 12, 13]. However, 2D MoSe₂ produced by mechanical exfoliation not only is single layer but also has a lot of thick flakes. Therefore, it is crucial to find a method to identify the thickness of 2D MoSe₂ accurately and rapidly.

Up to now, many methods have been studied, such as atom force microscope (AFM), Raman spectroscopy and optical microscopy (OM) [12–14]. Accurate enough, AFM and Raman spectroscopy [12] are commonly used to measure the thickness of 2D nanosheet, but they consume too much time, which might lead to the pollution of the samples before measurements [4, 13]. Compared with AFM and Raman spectroscopy, the optical technique performs more rapidly and conveniently [10, 15–17].

In this paper, OM method was used to identify the thickness of 2D $MoSe_2$ nanosheet with a few layers. Furthermore, the calculated and measured contrast was integral, which can be used to determine the $MoSe_2$ layer number accurately and rapidly.

2 Theoretical calculation

The key to identifying the thickness of 2D MoSe₂ nanosheet rapidly and accurately by OM is to correlate its thickness with its optical contrast. In order to calculate the contrast, it was considered the case of normal light incidence from air onto a three-layer structure consisting of two films (MoSe₂/SiO₂) on top of a third semi-infinite film (Si), as shown in Fig. 1. The optical contrast ($C(\lambda)$) of MoSe₂ on SiO₂/Si substrate was calculated by Fresnel equation under normal incident conditions [18]

$$C(\lambda) = \frac{I_0(\lambda) - I(\lambda)}{I_0(\lambda)} \tag{1}$$

where $I_0(\lambda) = |r_0(\lambda)|^2$ and $I(\lambda) = |r(\lambda)|^2$ are the reflected light intensities of the SiO₂/Si and MoSe₂/SiO₂/Si system, in which *r* is complex amplitude reflectance. Both intensities are light wavelength (λ) dependent.

$$r_0(\lambda) = \frac{r'_2 + r_3 e^{-2i\delta_2}}{1 + r'_2 r_3 e^{-2i\delta_2}}$$
(2)

$$r(\lambda) = \frac{r_1 + r_2 e^{-2i\delta_1} + r_3 e^{-2i(\delta_1 + \delta_2)} + r_1 r_2 r_3 e^{-2i\delta_2}}{1 + r_1 r_2 e^{-2i\delta_1} + r_2 r_3 e^{-2i\delta_2} + r_1 r_3 e^{-2i(\delta_1 + \delta_2)}}$$
(3)

where $r'_2 = \frac{n_0 - n_2}{n_0 + n_2}$, $r_1 = \frac{n_0 - n_1}{n_0 + n_1}$, $r_2 = \frac{n_1 - n_2}{n_1 + n_2}$, $r_3 = \frac{n_2 - n_3}{n_2 + n_3}$ are the relative indices of refraction. n_0 , n_1 , n_2 and n_3 are, respectively, the wavelength-dependent complex refractive indices of air, MoSe₂, SiO₂ and Si,

$$n_i = \operatorname{Re}(n_i) + \operatorname{Im}(n_i) \tag{4}$$

where $\operatorname{Re}(n_i)$ is the optical refractive index and $-\operatorname{Im}(n_i)$ is the absorption coefficient (i = 0, 1, 2, or 3). For n_0 (air) and n_2 (SiO₂), only the real part of the refractive index was used in the model. $\delta_1 = 2\pi d_1 n_1 / \lambda$ and $\delta_2 = 2\pi d_2 n_2 / \lambda$ are the phase shifts when light passes through MoSe₂ and SiO₂, respectively. $d = N \times d_1$ is the thickness of the MoSe₂ nanosheet, where N is the number of layers, d_1 is the



Fig. 1 Schematic depiction of light reflection in three-layered Fresnel's law model

thickness of single $MoSe_2$ layer, and d_2 is the thickness of the SiO₂ layer.

3 Results and discussion

Figure 2 shows the color plots of the calculated singlelayer MoSe₂ optical contrast on SiO₂/Si as a function of incident light wavelength with SiO₂ thickness ranging from 0 to 350 nm on Si substrate. From the calculations, it is clear that there are two bands with high, positive contrast for visible light with SiO₂ thickness of less than 350 nm. And the two bands with high contrast correspond to the thickness of SiO₂ in the range of 50–130 and 170–350 nm roughly. Considering that the red light and the green light are the major part when calculating the contrast, the silicon wafer around 90 and 275 nm should give the largest change of contrast. So, 275-nm SiO₂/Si substrates were selected in this experiment.



Fig. 2 Color plot of calculated optical contrast as a function of incident light wavelength from 400 to 750 nm and thickness of SiO_2 from 0 to 350 nm for single $MoSe_2$ nanosheet. Color bar representing optical contrast



Fig. 3 Theoretically calculated optical contrast of 1- to 4-layer $MoSe_2$ nanosheets as a function of incident light wavelength on SiO_2 (275 nm)/Si substrate

Figure 3 gives the theoretically calculated results of optical contrast spectra of $MoSe_2$ nanosheet with various atomic planes on SiO_2 (275 nm)/Si substrate. It is clear that the contrast value changes a lot along the incident light wavelength, depending on the number of $MoSe_2$ layers, and the most obvious contrast is in the range of green light wavelength. The integration of the contrast values in visible light regions is performed. The average contrast values of 1- to 4-layer $MoSe_2$ are 0.22, 0.33, 0.36 and 0.34, respectively, given by the integrated value divided by the visible light range. It makes the identification of the $MoSe_2$ thickness possible that the contrast value depends on the number of $MoSe_2$ layers.

To determine the relation between the spectra contrast and the thickness of the $MoSe_2$ nanosheet, natural $MoSe_2$ crystals with different layers were exfoliated mechanically and transferred onto the freshly cleaned 275-nm-thick SiO_2 -coated Si substrates. The optical images of the $MoSe_2$ nanosheet were captured at the exposure time of 80 ms by a Nikon MM-400 optical microscopy (OM). Figure 4a shows the surface image of a $MoSe_2$ nanosheet using an OM equipped with a color camera. Then, the sample was imaged using a BRUKER Dimension Icon atomic force microscopy (AFM) to measure the accurate thickness of the MoSe₂ nanosheet. Figure 4b, c is the corresponding 2D AFM images of the areas marked by white rectangles in Fig. 4a. The height values measured from the white solid lines (labeled as 1, 2 3, 4) in Fig. 4b, c are 0.72, 1.46, 2.23 and 2.88 nm (Fig. $5a_1-a_4$), respectively, and the thickness of single MoSe₂ layer is about 0.72 nm. The thickness value is consistent with that reported by others [19]. These height values obtained in the samples correspond to 1- to 4-layer MoSe₂ nanosheets, respectively. Figure $5b_1-b_4$ is the contrast profile of the yellow dashed rectangles highlighted in Fig. 4b, c generated by Image software. The contrast values of the 1- to 4-layer MoSe₂ nanosheets are 0.24, 0.33, 0.38 and 0.35, respectively. In addition to AFM, the spectrum of MoSe₂ nanosheets (1-4 layers) was also measured by spectroscopic ellipsometer (Horiba Uvisel FUV) under normal white light illumination. The optical spectra of 1- to 4-layer MoSe₂ of different illuminated wavelength fit well with the theoretically calculated results shown in Fig. 3.

Knowing the accurate thickness of the $MoSe_2$ nanosheet, it is able to make a correspondence with the optical contrast values. Figure 6 shows that the contrast of the theoretical calculation and experimental data changes with the number of $MoSe_2$ nanosheet layers. The calculated



Fig. 4 OM image of 1- to 4-layer MoSe₂ nanosheets on SiO₂ (275 nm)/Si substrate a and corresponding 2D AFM images of selected areas b, c



Fig. 5 Height profiles across white \mathbf{a}_1 solid Line 1, \mathbf{a}_2 solid Line 2, \mathbf{a}_3 solid Line 3 and \mathbf{a}_4 solid Line 4 (Δh being height difference of different layers) marked in Fig. 4b, c and contrast values of yellow \mathbf{b}_1 dashed Rectangle 1, \mathbf{b}_2 dashed Rectangle 2, \mathbf{b}_3 dashed Rectangle 3 and \mathbf{b}_4 dashed Rectangle 4 marked in Fig. 4b, c



Fig. 6 Theoretical and experimental contrast (C) values as a function of MoSe₂ layer number (N)

optical contrast fits the contrast analyzed from OM pictures very well. In addition, for the layer number of less than 3, contrast values can be fitted as C = 0.07N + 0.177. One can see that the contrast linearly increases with MoSe₂ layer number increasing, making the identification of MoSe₂ thickness by OM possible.

4 Conclusion

The contrast of different layers $MoSe_2$ on 275 nm SiO_2/Si was calculated, and the theoretical calculation was verified

by AFM and spectroscopic ellipsometer. The results show that the contrast values acquired by OM are consistent with the theoretically calculated contrast values, leading to identifying the thickness of MoSe₂ nanosheet accurately and rapidly possible. This work establishes a quantitative framework for detecting single and multiple layers of MoSe₂ and other 2D atomic crystals on top of various substrates. It is hoped to provide a lot of convenience on identifying the thickness of 2D materials in fundamental research and applications.

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